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71 Applicant: DELCO ELECTRONICS  
CORPORATION  
700 East Firmin Street  
Kokomo Indiana 46902(US)

72 Inventor: Akin, Timur  
504 W. Alexis No. 19

Toledo, Ohio 43612(US)  
Inventor: Maki, William M.  
9449 Crestridge Drive  
Fort Wayne, Indiana 46804(US)  
Inventor: Myers, Bruce A.  
4801 Pumpkinvine Drive  
Kokomo, Indiana 46902(US)  
Inventor: Palanisamy, Ponnusamy  
5004 Gettysburg Drive  
Kokomo, Indiana 46902(US)

74 Representative: Haines, Arthur Donald et al  
Patent Section Vauxhall Motors Limited 1st  
Floor Gideon House 26 Chapel Street  
Luton, Bedfordshire LU1 2SE(GB)

54 Integrated circuit/heat sink interface device.

57 An interface device (210), for thermally coupling an integrated circuit chip (212) to a heat sink (214), comprises a first material (216) characterized by high thermal conductivity, such as copper, wherein the copper (216) completely surrounds a plurality of inner core regions. The plurality of inner core regions contain a low coefficient of thermal expansion material (218) and are primarily disposed in the copper material (216) in the region directly under the integrated circuit chip (212). Therefore, the low expansion regions retard thermal expansion of the interface device (210) during exposure to variations in the temperature, yet there are continuous paths of

copper provided between the integrated circuit chip (212) and heat sink (214) so as to promote efficient heat transfer between the integrated circuit chip (212) to the heat sink (214) through the high conductivity copper (216). In addition, a dielectric layer (228) is provided between said integrated circuit chip (212) and heat sink (214), when necessary, using this invention. This interface device (210) is characterized by enhanced thermal dissipation yet provides a compatible coefficient of thermal expansion with the silicon integrated circuit chip (212) and underlying heat sink (214).

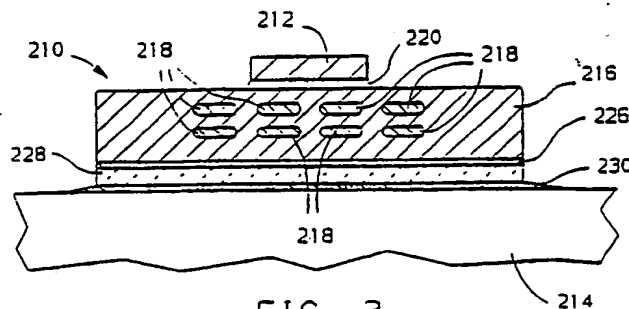


FIG. 3

## INTEGRATED CIRCUIT/HEAT SINK INTERFACE DEVICE

This invention relates to an interface device used to transfer heat away from a mounted electronic component. In particular, this invention relates to an interface device for transferring heat generated by a high-power silicon integrated circuit chip to a heat sink as specified in the preamble of claim 1, for example as disclosed in US-A-4,427,993.

### Background of the Invention

The environmental conditions which integrated circuits must endure during operation are severe, particularly in an automotive environment. During the operation of an automobile, the integrated circuit chips are exposed to large variations in temperature arising from not only the changes in ambient atmospheric temperature, but also from the variations in the operating temperature generated by the automobile itself. Generally, an automobile manufacturer requires these integrated circuits to reliably perform while experiencing repeated cycling between ambient temperatures of  $-40^{\circ}\text{C}$ . and  $+125^{\circ}\text{C}$ . Therefore, it is necessary that the integrated circuit be capable of withstanding these temperature extremes without detriment to its structural or electrical integrity.

In addition, power-generating integrated circuits are particularly problematic in that they, accordingly, also generate substantial amounts of heat during generation of the power. This heat generation increases the temperature of the chip and may detrimentally affect circuit performance and/or cause chip failure. In addition, the power-generating integrated circuit may need to be dielectrically isolated from the surrounding components. These detrimental effects are compounded when combined with the temperature extremes experienced by the integrated circuit during operation of an automobile. Therefore, it is desirable to provide means for maintaining a constant temperature of the integrated circuit chip despite any variations in temperature within and surrounding the chip. A common solution involves soldering a chip to a heat sink. Generally the heat sinks are formed from aluminium, which is relatively inexpensive, or alternatively copper, which is relatively expensive.

However, a shortcoming of this approach is that, during the exposure to the variations in temperature, the solder used to couple the integrated circuit chip and heat sink will fracture due to stresses arising from the differences in thermal expansion rates of the various materials. The coefficient of thermal expansion for silicon is approximately

equal to  $3.5 \times 10^{-6}/^{\circ}\text{C}$ , while the coefficients of thermal expansion for copper or aluminium are approximately equal to  $17.7 \times 10^{-6}/^{\circ}\text{C}$  and  $24 \times 10^{-6}/^{\circ}\text{C}$ , respectively. Generally, the solder will fracture most often at the corners of the chip where the stresses are concentrated. These fractures are particularly undesirable as they increase the thermal resistance between the chip and the heat sink, which in turn causes the temperature of the chip to rise because of retarded heat transfer to the heat sink. This phenomenon further adversely affects the performance of the integrated circuit thereby promoting failure of the integrated circuit chip.

Alternative solutions to the temperature problem have also been disclosed by the prior art and generally involve the use of an interface device, or buffer, between the integrated circuit chip and heat sink which is characterized by a high thermal conductivity, or correspondingly, relatively low thermal resistance. In addition, it is desirable that the interface device have a coefficient of thermal expansion which is intermediate between that of the integrated circuit chip and that of the heat sink. In such a structure, the integrated circuit is soldered to one side of the interface device and the heat sink to the other side of the interface device. Molybdenum and tungsten have been commonly used for interface devices because of their appropriate heat transfer and expansion characteristics. These interface devices have been a satisfactory solution to the problem, however it is desirable to provide a less expensive alternative. In particular, for automotive applications, molybdenum and tungsten are considered too expensive for commercial use.

Another type of interface device has been proposed in United States Patent Application Serial No. 191,441, entitled "Integrated Circuit Heat Sink Interface Apparatus" to Akin et al, wherein an inner core of low-expansion material is surrounded everywhere by a copper outer layer characterized by high thermal conductivity. The integrated circuit contacts the copper layer at a region which is over the inner core layer of low-expansion material. The heat sink contacts the copper layer on an opposite side of the integrated circuit. This arrangement is of relatively low cost and permits rapid conductivity of the generated heat from the integrated circuit through the copper outer layer around the inner core layer, whilst the low-expansion material retards the overall thermal expansion of the interface device. Although this design is satisfactory, it would be desirable to provide an interface device which permits the most efficient heat transfer directly from the integrated circuit to the heat sink, rather than around the inner core layer as in this previous

method.

Therefore, it is desirable to provide an interface device which provides direct thermal coupling between an integrated circuit and heat sink, and which is durable, reliable over varying temperature conditions, characterized by an intermediate coefficient of expansion, and readily amenable to automotive production techniques.

### Summary of the Invention

An interface device according to the present invention is characterised by the features specified in the characterising portion of claim 1.

It is, therefore, an object of this invention to provide an efficient interface device suitable for thermally coupling an integrated circuit directly to a heat sink, which is durable such that it can reliably withstand the extreme operating temperatures present in an automotive environment. It is a further object of this invention to provide an interface device which is characterized by a coefficient of thermal expansion intermediate between the coefficients for the integrated circuit and the heat sink.

In addition, it is an object of this invention that such an interface device be compatible with means for providing dielectric isolation between an appropriate integrated circuit chip and heat sink. Lastly, it is still a further object of this invention to provide an interface device which is of relatively low cost and readily amenable to automotive production techniques.

In accordance with the preferred embodiment of this invention, these and other objects and advantages are accomplished as follows.

In a preferred embodiment of the present invention, the interface device for thermally coupling an integrated circuit to a heat sink comprises a first material characterized by high thermal conductivity such as copper, wherein the copper completely surrounds a plurality of inner core regions. The plurality of inner core regions comprise a low coefficient of expansion material, preferably an iron-nickel alloy, such as Invar or Kovar. In addition, the plurality of inner core regions are primarily disposed in the copper material in the region directly under the integrated circuit, thereby retarding expansion of the interface device during exposure to variations in the temperature.

In use, a silicon integrated circuit chip is soldered to an upper surface of the interface device, and an aluminium or copper heat sink is bolted to a lower surface of the interface device. Preferably, silicon grease is placed between the lower surface of the interface device and the heat sink so as to promote heat flow through the interface device to the heat sink. Therefore, the heat generated by the

integrated circuit chip passes directly into the interface device, and primarily into the high thermally-conductive copper layer wherein the heat transfers rapidly through the copper into the heat sink. The low-expansion material retards the overall expansion rate of the interface device.

An inventive feature of this device is that the plurality of low-expansion regions retard the expansion rate of the device where it is most needed under the silicon chip, but do not hamper the heat flow from the silicon chip to the heat sink. With previous designs, the low-expansion material which is typically characterized by high thermal resistivity, acted as a barrier against effective heat transfer out of the chip. The heat was forced to flow around the low-expansion material/high-resistivity material, resulting in an inefficient method of heat transfer. With this design, the heat is not required to flow around the low-expansion material, as there are continuous paths of high-conductivity material directly from the integrated circuit chip to the heat sink. This interface device is characterized by enhanced thermal dissipation yet provides a compatible coefficient of thermal expansion with the silicon integrated circuit and underlying heat sink.

The coefficient of thermal expansion of the preferred interface device having a cross-sectional area which is approximately 80 percent copper and approximately 20 percent an iron-nickel alloy characterized by about 42 percent nickel, was found to be approximately  $9 \times 10^{-6}/^{\circ}\text{C}$ . This coefficient of thermal expansion is sufficiently compatible with that of silicon to allow the solder joint between the chip and the interface device to remain intact during operation without fracturing for a substantial number of temperature cycles between  $-40^{\circ}\text{C}$ . and  $+125^{\circ}\text{C}$ .

Other objects and advantages of this invention will be better appreciated from a detailed description thereof, which follows.

### Brief Description of the Drawings

Figure 1 is cross-sectional view of an interface device which may be used for thermally coupling an integrated circuit chip and heat sink in accordance with a preferred embodiment of this invention.

Figure 2 is a cross-sectional view of an interface device in accordance with an alternative and equally preferred embodiment of this invention.

Figure 3 is a cross-sectional view of the interface device shown in Figure 2 wherein a dielectric isolation means is also provided between the interface device and the heat sink.

Figure 4 is a plan view of a perforate layer of material characterized by a low coefficient of ther-

mal expansion overlaying a layer of material characterized by high thermal conductivity.

Figure 5 is a cross-sectional view of the interface device shown in Figure 1.

#### Detailed Description

This invention comprises an interface device which is used to thermally couple an integrated circuit chip to a heat sink. The preferred interface device is thermally efficient in that heat generated from the integrated circuit passes directly through the interface device into the heat sink. In addition, the preferred device is characterized by a coefficient of thermal expansion intermediate between the respective coefficients of thermal expansion for the integrated circuit and the heat sink. The preferred interface device is durable in that it can reliably withstand the extreme operating temperatures present in an automotive environment without detriment to its structural or electrical integrity. In addition, this preferred interface device is conducive in cost and manufacturability to automotive production techniques.

A preferred embodiment of the interface device 10 is shown in Figure 1. The interface device 10 is coupled to an integrated circuit 12 and an underlying heat sink 14. The interface device 10 primarily comprises a first material 16 which is characterized by high thermal conductivity or low thermal resistance. A second material 18 which is characterized by a low coefficient of thermal expansion is dispersed as a plurality of regions throughout the first material 16. This first material 16 completely surrounds each region of second material 18.

The preferred first material 16 which is characterized by a high thermal conductivity is copper, however other materials characterized by high thermal conductivity, such as aluminium, may also be used. In addition, a consideration when choosing the first material 16 is that the first material 16 must be compatible with the second material 18 which will be dispersed throughout the first material 16. For the first material 16, copper is preferred because of its high thermal conductivity, cost and ease of manufacturability.

The plurality of second material 18 regions comprise a material characterized by a low coefficient of thermal expansion, such as an iron-nickel alloy. In particular, an iron-nickel alloy comprising approximately 42 percent nickel and approximately 58 percent iron such as Invar is preferred. However, other materials which are characterized by a low coefficient of thermal expansion and which are compatible with the surrounding first material 16, may also be used.

As shown in Figure 1, a silicon integrated circuit chip 12 is soldered, the solder being denoted

as layer 20, to an upper surface 22 of the primarily copper interface device 10 and an aluminium or copper heat sink 14 is bolted to a lower surface 24 of the primarily copper interface device 10. The preferred solder is a 25/75 tin-lead type for manufacturability and availability purposes, however other suitable solders may also be used. Preferably, silicon grease (denoted as layer 26) is placed between the lower surface 24 of the interface device 10 and the heat sink 14. The silicon grease 26 is preferred since it permits heat transfer through to the heat sink 14 from the interface device 10, however, other suitable materials which will provide the appropriate heat transfer through to the heat sink 14 from the interface device 10 may also be used, such as suitable epoxy resins or solder.

Preferably, the low-expansion second material regions 18 are primarily located under the silicon integrated circuit chip 12 in the surrounding copper or other appropriate first material 16. It is desirable to position the low-expansion second material regions 18 primarily under the silicon chip 12 because the silicon expands at a much lower rate, as its temperature is increased, than the other materials. Therefore, the expansion of the interface device 10 is retarded most where it is required, i.e., under the silicon chip 12, with this design.

In addition, the number of low-expansion second material regions 18 may vary within the surrounding copper material 16. As shown in Figure 1, there are four low-expansion regions 18 primarily situated under the integrated circuit chip 12 within the surrounding copper material 16. The arrows indicate the pattern of heat flow from the integrated circuit chip 12 to the heat sink 14 through the interface device 10. With this device 10, heat transfer occurs most efficiently. The heat generated by the integrated circuit chip 12 flows directly into the interface device 10, dissipating through the highly conductive surrounding copper layer 16 wherein the heat transfers rapidly through the copper layer 16 into the heat sink 14.

A truly inventive feature of this device 10 is that the low-expansion regions 18 retard the expansion rate of the device 10 where it is most needed under the silicon chip 12, but do not hamper the heat flow from the silicon chip 12 to the heat sink 14 since the highly conductive surrounding copper layer 16 is provided generally everywhere throughout the device 10. With previous designs, the low-expansion material which is typically characterized by high thermal resistivity, acted as a barrier against effective heat transfer out of the chip 12. The heat was forced to go around the low-expansion material/high-resistivity material, resulting in an inefficient method of heat transfer. With this design, the heat does not need to go around the low-expansion second material 18, as there are con-

tinuous paths of high conductivity copper straight from the integrated circuit chip 12 to the heat sink 14.

Therefore, this interface device 10 is characterized by enhanced and efficient thermal dissipation yet provides a compatible coefficient of thermal expansion with the silicon integrated circuit 12 and underlying heat sink 14.

As shown in Figure 2, an alternative and equally preferred embodiment 110 of this invention is also illustrated. In this interface device 110, there are essentially two rows of low-expansion second material 118 enveloped by surrounding copper or other high-conductivity material 116. This device 110 permits enhanced heat transfer through the surrounding copper 116 and is characterized by an appropriate expansion rate. Theoretically, a device 110 in accordance with this invention, could have as few as two low-expansion regions 118 separated by the copper 116 under a silicon chip 112 thereby providing a single direct path for heat transfer from the silicon chip 112 to a heat sink 114, or a multitude of low-expansion regions wherein the only limitations would be manufacturing and feasibility considerations.

This interface device 110, shown as device 210 in Figure 3, may also be used when dielectric isolation is required, such as between a power-producing integrated circuit 212 and a heat sink 214. In this preferred embodiment of Figure 3, the dielectric isolation is provided by a polyimide layer 228, which has a thermally-conductive material dispersed throughout for enhanced thermal conductivity characteristics. The polyimide layer 228 is attached to the heat sink 214 by a very thin layer of thermally-conductive adhesive 230.

These two relatively high thermal resistance layers, i.e., the polyimide layer 228 and the conductive adhesive layer 230, are manufactured to be very thin to minimize the detrimental effects associated with their inherently high thermal resistance. The dielectric means, or polyimide layer 228, is preferably formed from a plastics dielectric material, such as Kapton. It is even more preferred that this dielectric layer 228 have dispersed throughout a suitable dielectric material having relatively high thermal conductivity, such as alumina, aluminum nitride or beryllium oxide. The thermally-conductive adhesive layer 230 used to attach the dielectric layer 228 to the heat sink 214 is preferably formed from an epoxy resin paste having silver or other appropriate thermally-conductive medium dispersed throughout. This medium may also be electrically conductive since the dielectric isolation is provided by layer 228. The silver-filled epoxy resin layer 230 is used for its convenience and availability, however other materials such as commercially-available B-staged epoxy resins,

which are partially cured pastes, may also be used.

As shown in Figure 3, a layer 226 of solder or other attachment means is required between the interface device 210 and dielectric layer 228. It is preferred that this solder layer 226 be formed from a 60/40 tin-lead solder. This is preferred because the solder layer 220 used to attach the integrated circuit 212 to the interface device 210 is a 25/75 lead-tin solder and this combination of solders having differing melting temperatures permits ease of manufacturability without detrimental effects to the complete structure. In addition, a flash metallization layer (not shown) may be required on the dielectric layer 228 to promote adhesion between the dielectric layer 228 and the solder layer 226, as well as between the dielectric layer 228 and the thermally-conductive adhesive layer 230. The structure shown in Figure 3 provides dielectric isolation when necessary between an integrated circuit chip 212 and heat sink 214.

The coefficient of thermal expansion of the preferred interface device should be no more than about  $10 \times 10^{-6}/^{\circ}\text{C}$ . This is the maximum expansion rate that is desirable. The coefficient of thermal expansion for the silicon integrated circuit chip is approximately equal to about  $3.5 \times 10^{-6}/^{\circ}\text{C}$ , whilst the coefficient of thermal expansion for an aluminium heat sink is approximately  $24 \times 10^{-6}/^{\circ}\text{C}$ . In addition, the coefficients of thermal expansion for copper and an iron-nickel alloy containing approximately 42 percent nickel are  $17.7 \times 10^{-6}/^{\circ}\text{C}$  and about  $2.7 \times 10^{-6}/^{\circ}\text{C}$ , respectively.

An empirically derived equation to determine the average coefficient of thermal expansion (CTE) of the interface device is:

Average CTE of interface device =  $0.62 \times \% \text{ Copper} \times \text{CTE of Copper} + \% \text{ low expansion material (LEM)} \times \text{CTE of LEM}$

where 0.62 is the ratio of the Young's Modulus of elasticity of copper to that of an iron-nickel alloy having approximately 42 percent nickel.

An interface device having a cross-sectional area which is approximately 80 percent copper and approximately 20 percent an iron-nickel alloy containing about 42 percent nickel, such as either device 10, 110 or 210 shown in Figures 1, 2 and 3, is found to have a coefficient of thermal expansion of approximately  $9 \times 10^{-6}/^{\circ}\text{C}$ . This coefficient of thermal expansion is sufficiently compatible with that of silicon to allow the solder joint 20, 120 or 220 between the chip 12, 112 or 212 and the interface device 10, 110 or 210 to remain intact during operation without fracturing for a substantial number of temperature cycles between  $-40^{\circ}\text{C}$  and  $+125^{\circ}\text{C}$ .

There are several methods proposed for forming this interface device. A first method comprises the steps of sandwiching a perforate layer of

low-expansion material between two outer layers of copper and appropriately heating the materials so as to metallurgically bond the materials together. The perforate layer of low-expansion material may be formed by punching, piercing, dissolution or any other suitable means. In addition, a perforate layer 50, as shown in Figure 4, overlaying a single layer 52 of copper or other appropriate high thermal conductivity material, is preferably provided only in a centre region of the sandwiched layers (only the bottom layer 52 is shown in Figure 4 for clarity), so as to correspond to the region where the integrated circuit chip will be disposed. During the heating step, the copper flows into the perforate areas 54 of the low-expansion material 50, thereby completely enveloping the low expansion material 50. The resulting material is then sliced appropriately through all three sandwiched layers such that a resulting cross-section through the device is illustrated in Figure 5. Figure 5 shows the interface device 10 illustrated in Figure 1 which comprises a plurality of low-expansion second material regions 18 which were formed from the perforate layer (50 in Figure 4), surrounded by the high thermal conductivity material 16 which flowed into the perforations during heat treatment.

Alternatively, the device having a cross-section as shown in Figures 2 or 3 may be formed by sandwiching a plurality of perforate layers between alternating layers of copper. Theoretically, the device could have a multitude of these layers, the only limit being manufacturability and feasibility. However, a device having two perforate layers sandwiched between three alternating layers of copper is preferred.

As another alternative, the device could be fabricated by sandwiching strips of low-expansion wire between alternating layers of copper, and subsequently heat treating the sandwich thus formed to metallurgically bond the materials together. Again this would produce the desired result wherein the high conductivity copper completely surrounds a plurality of regions containing the low-expansion material. Although this alternative embodiment performs satisfactorily, it is not as preferred as the perforated embodiment which provides better control of the coefficient of thermal expansion properties of the device in both lateral directions, i.e., the x and y-axis of the device.

This invention readily provides an interface device which promotes efficient heat transfer between a heat-generating integrated circuit chip and a heat sink, whilst also providing an intermediate and compatible coefficient of thermal expansion between the two components.

## Claims

1. An interface device (10;110;210) for coupling an integrated circuit chip (12;112;212) having a first coefficient of thermal expansion to a second apparatus (14;114;214) having a second coefficient of thermal expansion, the interface device (10;110;210) comprising: a first material (16;116;216) characterized by high thermal conductivity, and a second material (18;118;218) characterized by a low coefficient of thermal expansion, said first material (16;116;216) being bonded to said second material (18;118;218) so that said interface device (10;110;210) has an effective coefficient of thermal expansion intermediate between said first and second coefficients of thermal expansion, characterised in that said second material (18;118;218) is completely enveloped within the first material (16;116;216) and forms regions, which are either discrete regions or interlinked regions, separated from one another by zones of said first material (16;116;216), with a majority of said regions being disposed throughout said first material (16;116;216) under the integrated circuit chip (12;112;212), and said first material (16;116;216) contacts the integrated circuit chip (12;112;212) directly and provides a continuous thermal bridge in at least one region (54) between the integrated circuit chip (12;112;212) and the second apparatus (14;114;214).
2. An interface device (10;110;210) according to claim 1, in which said first material (16;116;216) comprises copper.
3. An interface device (10;110;210) according to claim 1 or 2, in which said second material (18;118;218) comprises an iron-nickel alloy.
4. An interface device (10;110;210) according to claim 3, in which said second material (18;118;218) comprises an alloy containing approximately 42 percent nickel and approximately 58 percent iron.
5. An interface device (10;110;210) according to any one of claims 1 to 4, in which there are up to four regions of said second material (18;118;218) disposed under the integrated circuit chip (12;112;212).
6. An interface device (210) according to any one of the preceding claims, characterised in that the interface device (210) includes a thermally-conductive dielectric layer (228) which is secured in direct contact with said second apparatus (214).
7. An interface device (210) according to claim 6, characterised in that the dielectric layer (228) consists of a polyimide having dispersed throughout a thermally-conductive material, and appropriate adhesive means (230) attaching said polyimide to said second apparatus (214).
8. An integrated circuit arrangement comprising: a silicon, monolithic integrated circuit chip

(12;112;212); an aluminium heat sink (14;114;214),  
and an interface device (10;110;210) according to  
any one of the preceding claims, said interface  
device (10;110;210) having a thermal conductivity  
similar to the thermal conductivity of said first ma- 5  
terial (16;116;216) of said device (10;110;210).

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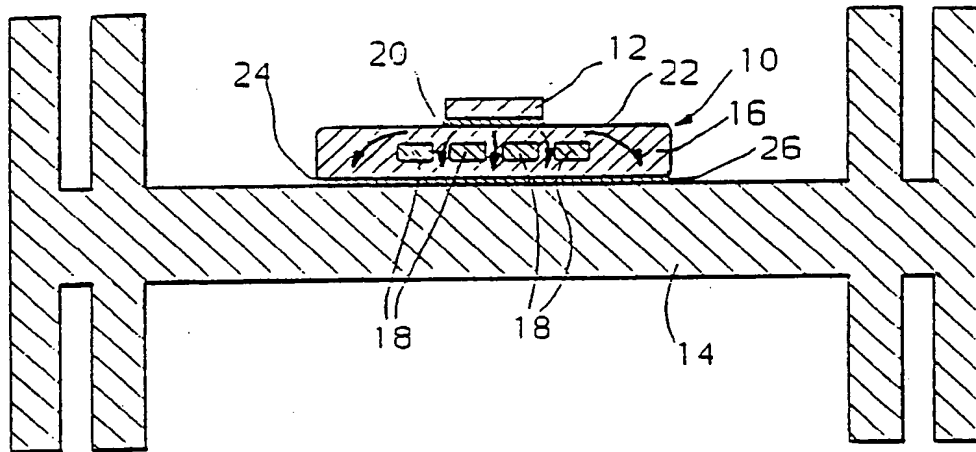


FIG. 1

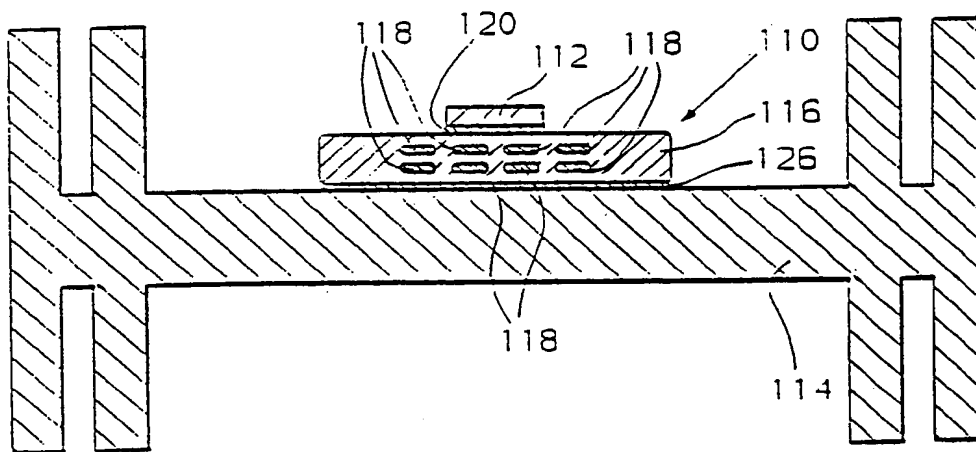
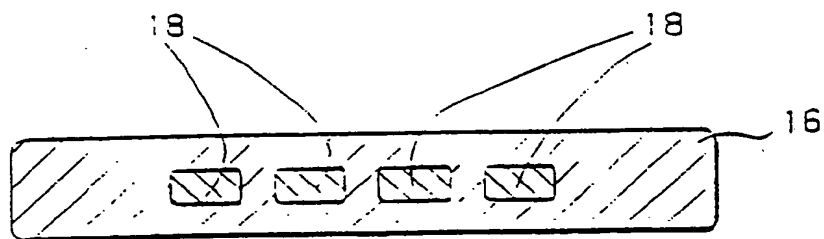
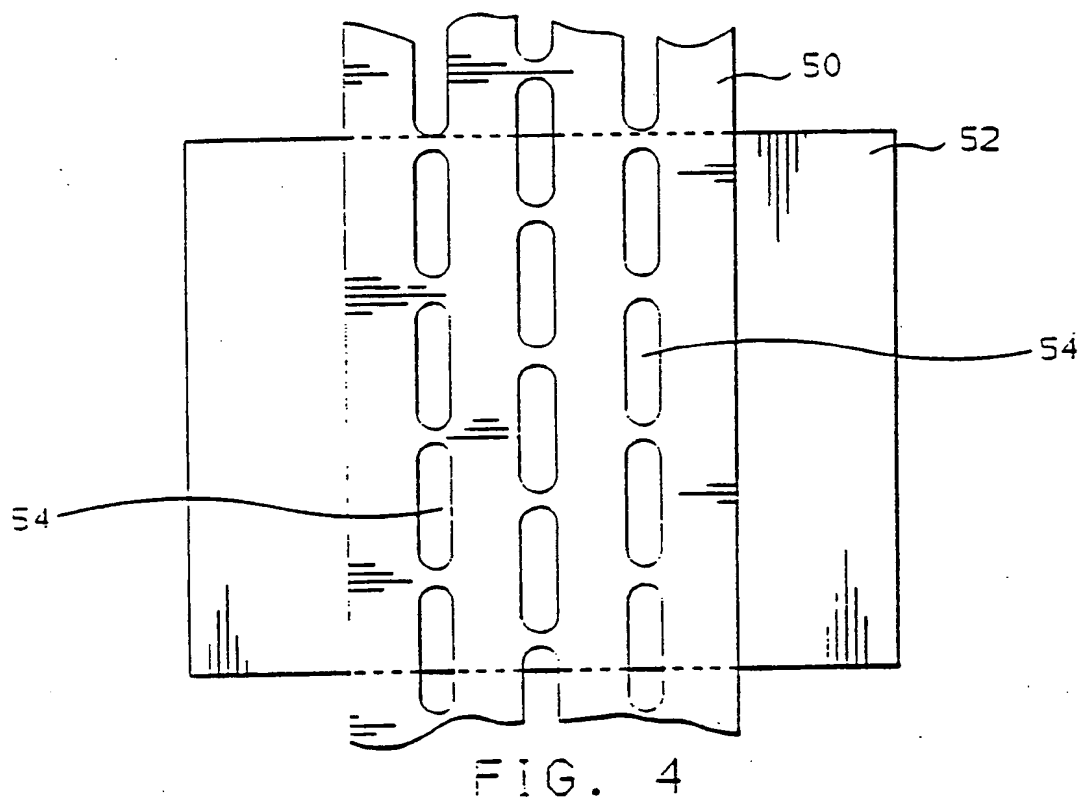
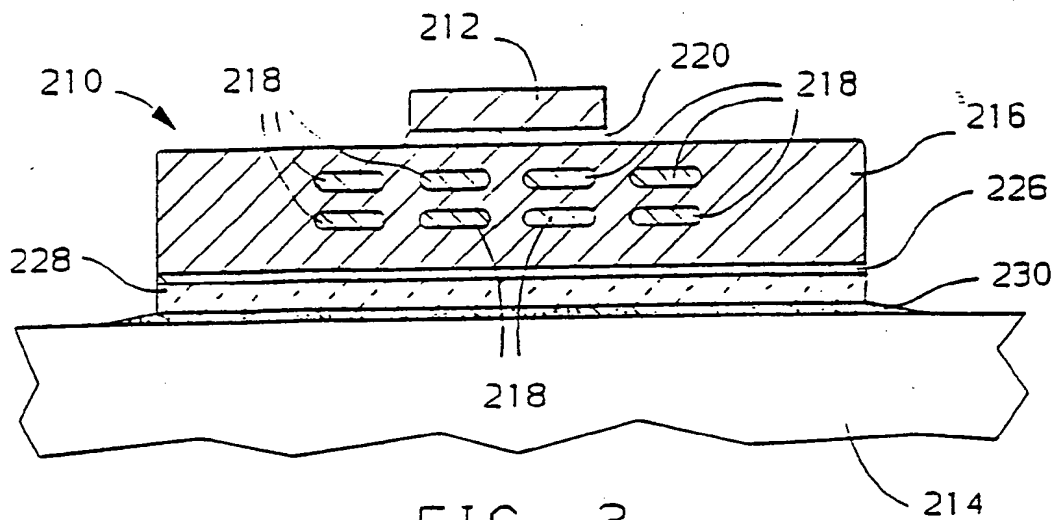


FIG. 2





(19)



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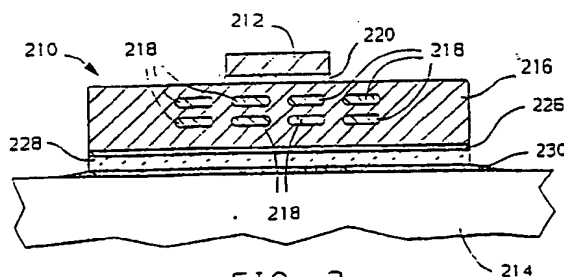
(51) Int. Cl.<sup>5</sup>: **H01L 23/36**

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27.03.91 Bulletin 91/13(71) Applicant: **DELCO ELECTRONICS CORPORATION**  
700 East Firmin Street  
Kokomo Indiana 46902(US)(72) Inventor: Akin, Timur  
504 W. Alexis No. 19  
Toledo, Ohio 43612(US)  
Inventor: Maki, William M.  
9449 Crestridge Drive  
Fort Wayne, Indiana 46804(US)  
Inventor: Myers, Bruce A.  
4801 Pumpkinvine Drive  
Kokomo, Indiana 46902(US)  
Inventor: Palanisamy, Ponnusamy  
5004 Gettysburg Drive  
Kokomo, Indiana 46902(US)(74) Representative: Haines, Arthur Donald et al  
Patent Section Vauxhall Motors Limited 1st  
Floor Gideon House 26 Chapel Street  
Luton, Bedfordshire LU1 2SE(GB)(54) **Integrated circuit/heat sink interface device.**

(57) An interface device (210), for thermally coupling an integrated circuit chip (212) to a heat sink (214), comprises a first material (216) characterized by high thermal conductivity, such as copper, wherein the copper (216) completely surrounds a plurality of inner core regions. The plurality of inner core regions contain a low coefficient of thermal expansion material (218) and are primarily disposed in the copper material (216) in the region directly under the integrated circuit chip (212). Therefore, the low expansion regions retard thermal expansion of the interface device (210) during exposure to variations in the temperature, yet there are continuous paths of copper provided between the integrated circuit chip (212) and heat sink (214) so as to promote efficient heat transfer between the integrated circuit chip (212) to the heat sink (214) through the high conductivity copper (216). In addition, a dielectric layer (228) is provided between said integrated circuit chip

(212) and heat sink (214), when necessary, using this invention. This interface device (210) is characterized by enhanced thermal dissipation yet provides a compatible coefficient of thermal expansion with the silicon integrated circuit chip (212) and underlying heat sink (214).

**FIG. 3****EP 0 385 605 A3**



European Patent  
Office

## EUROPEAN SEARCH REPORT

Application Number

DOCUMENTS CONSIDERED TO BE RELEVANT			EP 90301513.9
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.5)
X	PATENT ABSTRACTS OF JAPAN, unexamined applications, E field, vol. 4, no. 185, December 19, 1980 THE PATENT OFFICE JAPANESE GOVERNMENT page 65 E 38 * Koaki-No. 55-127 044 (HITACHI SEISAKUSHO K.K.) *	1,2,8	H 01 L 23/36
X	PATENT ABSTRACTS OF JAPAN, unexamined applications, E field, vol. 5, no. 34, March 4, 1981 THE PATENT OFFICE JAPANESE GOVERNMENT page 160 E 48 * Kokai-No. 55-162 249 (HITACHI SEISAKUSHO K.K.) *	1,2	
			TECHNICAL FIELDS SEARCHED (Int. Cl.5)
			H 01 L 23/00
The present search report has been drawn up for all claims			
Place of search VIENNA		Date of completion of the search 22-01-1991	Examiner BERGER
CATEGORY OF CITED DOCUMENTS X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document		T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons A : member of the same patent family, corresponding document	